## PATENT APPLICATION

**RESPONSE UNDER 37 CFR §1.116** EXPEDITED PROCEDURE **TECHNOLOGY CENTER ART UNIT 1675**  #11/c 16/03 NE

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Takao ABE et al.

Group Art Unit: 1765

Application No.:

09/743,982

Examiner:

M.A. Anderson

Filed: January 18, 2001

Docket No.:

108360

For:

SILICON SINGLE CRYSTAL AND WAFER DOPED WITH GALLIUM AND

METHOD FOR PRODUCING THEM

## AMENDMENT AFTER FINAL REJECTION UNDER 37 CFR §1.116

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

In reply to the February 4, 2003 Office Action, please amend the above-identified application as follows:

## IN THE CLAIMS:

Please replace claims 35-45 as follows:

35. (Twice Amended) The silicon single crystal solar cell according to Claim 30. wherein loss of overall conversion efficiency due to photo-degradation is 0.5 % or less.

- 36. (Twife Amended) The silicon single crystal solar cell according to Claim 32, wherein loss of overall conversion efficiency due to photo-degradation is 0.5 % or less.
- 37. (Twice Amended) A method for production of silicon single crystal to which Ga is added according to Czochralski method wherein Ga is added in a silicon melt in a crucible, a seed crystal is brought into contact with the silicon melt and is pulled with rotating